

TSMC-99-287



January 3, 2000

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To: Commissioner of Patents and Trademarks
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572
20 McIntosh Drive
Poughkeepsie, N.Y. 12603

JAN 27 2000
TECHNOLOGY CENTER 2800

Subject:

Serial No. 09/434,563 11/12/99

H.J. Tao, H.J. Lin, F.C Chen

METHOD TO CONTROL GATE CD

Grp. Art Unit: 2825

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56. Copies of each document is included herewith

U.S. Patent 5,913,102 to Yang, "Method for Forming
Patterned Photoresist Layers with Enhanced Critical Dimension
Uniformity", discloses a system for controlling CD using a
measurement parameter and a control parameter.


U.S. Patent 5,674,409 to Muller, "Nanolithographic Method
of Forming Fine Lines", discloses a photoresist trimming
process that uses ashing.

U.S. Patent 5,057,187 to Shinagawa et al., "Ashing Method for Removing an Organic Film on a Substance of a Semiconductor Device Under Fabrication", discloses a method of controlling an ashing process

U.S. Patent 4,717,445 to Leung, "Etch Bias Monitoring Technique", discloses an etch bias monitoring technique.

U.S. Patent 5,804,460 to Bindell et al., "Linewidth Metrology of Integrated Circuit Structures", discloses a method for measuring photoresist line widths.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', with a stylized flourish extending to the right.

Stephen B. Ackerman,
Reg. No. 37661